

## Electronic Supplementary Information

### Synthesis and Characterization of $(\text{Ga}_{1-x}\text{Zn}_x)(\text{N}_{1-x}\text{O}_x)$ Nanocrystals with a Wide Range of Compositions

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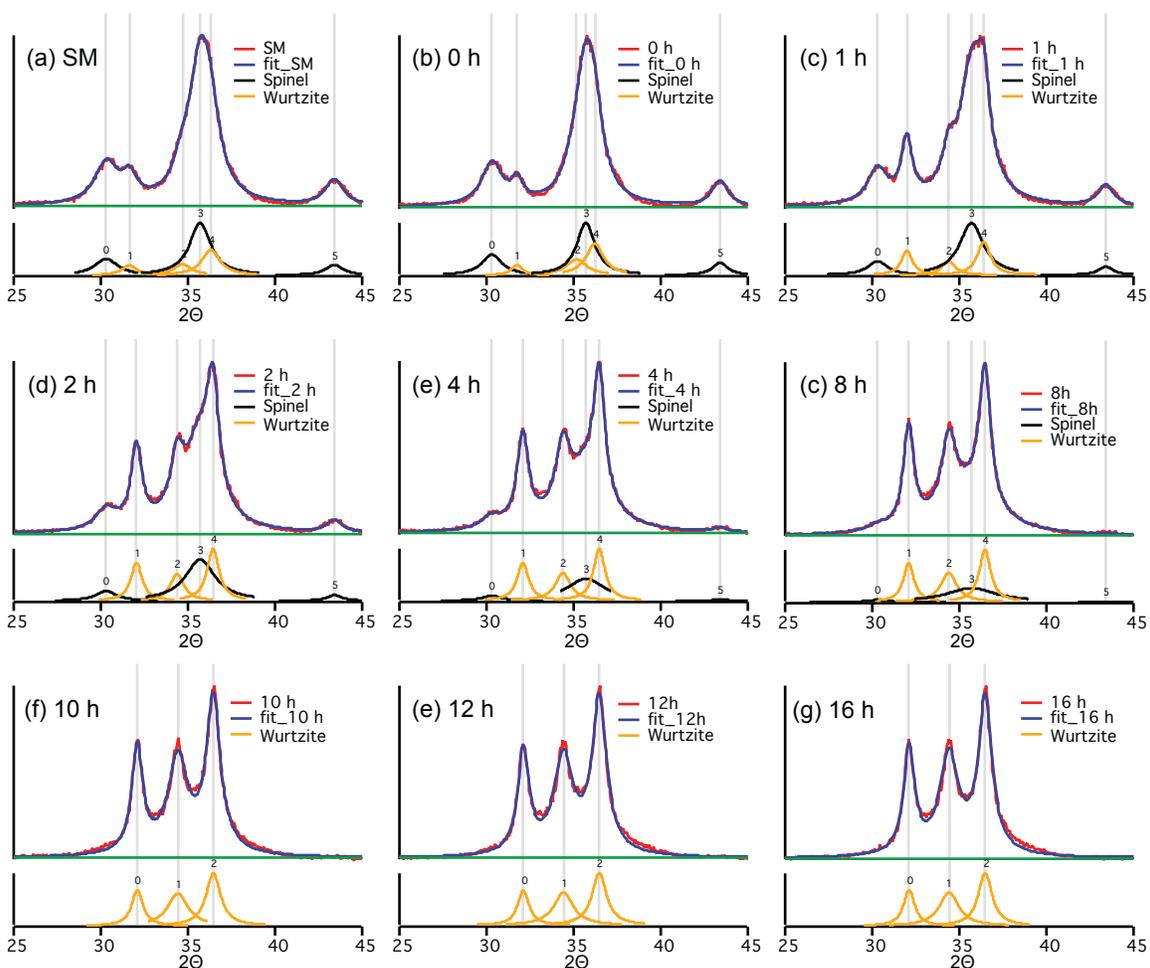


Figure S1. Fitting of XRD patterns of the nitrated products for 0–16 hours at 650 °C from a starting material mixture with  $\text{Zn}/(\text{Zn}+\text{Ga})=0.39$ .

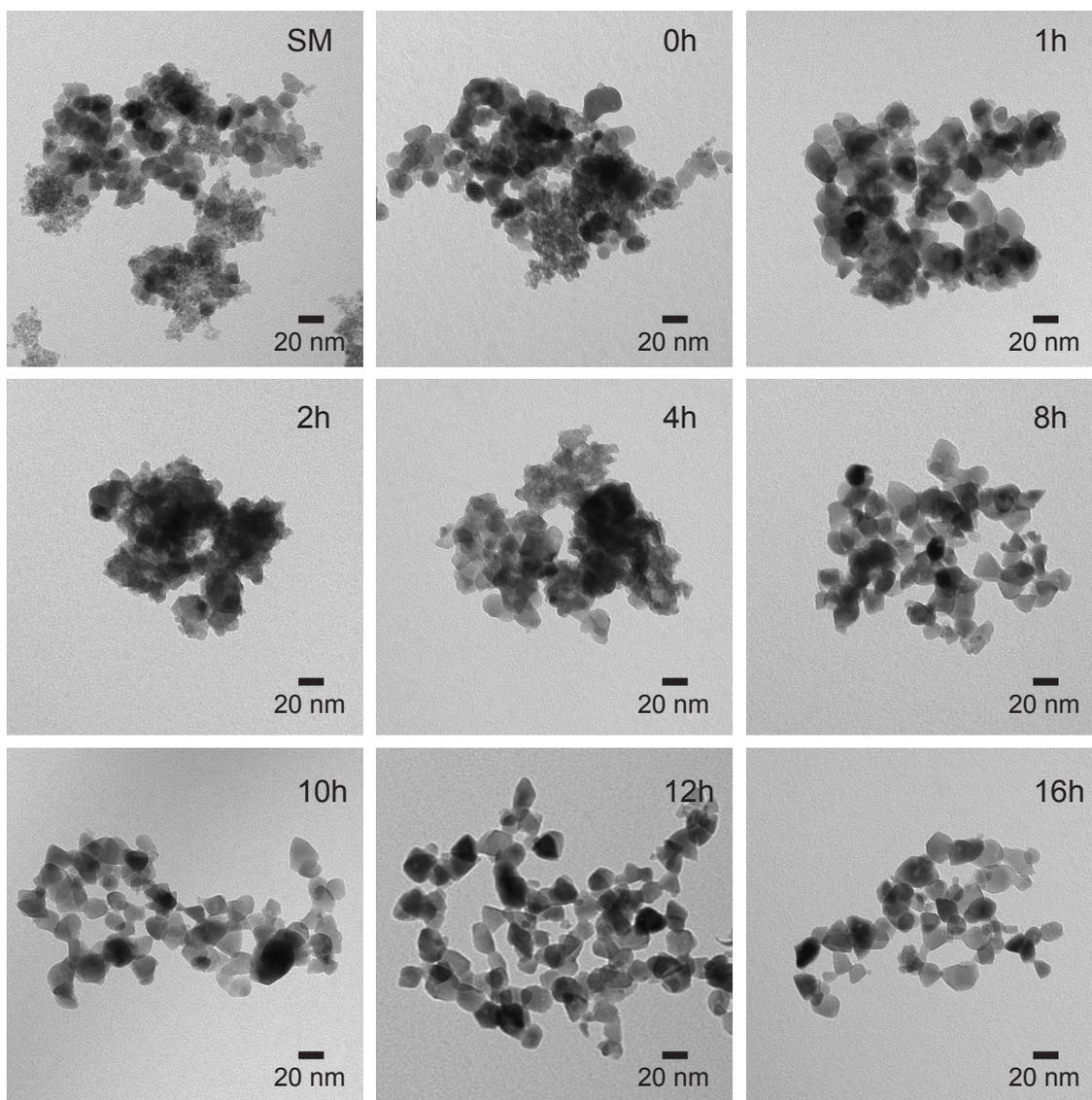


Figure S2. Low-magnification TEM images of the nitrided products for 0–16 hours at 650 °C from a starting material mixture with  $Zn/(Zn+Ga)=0.39$ .

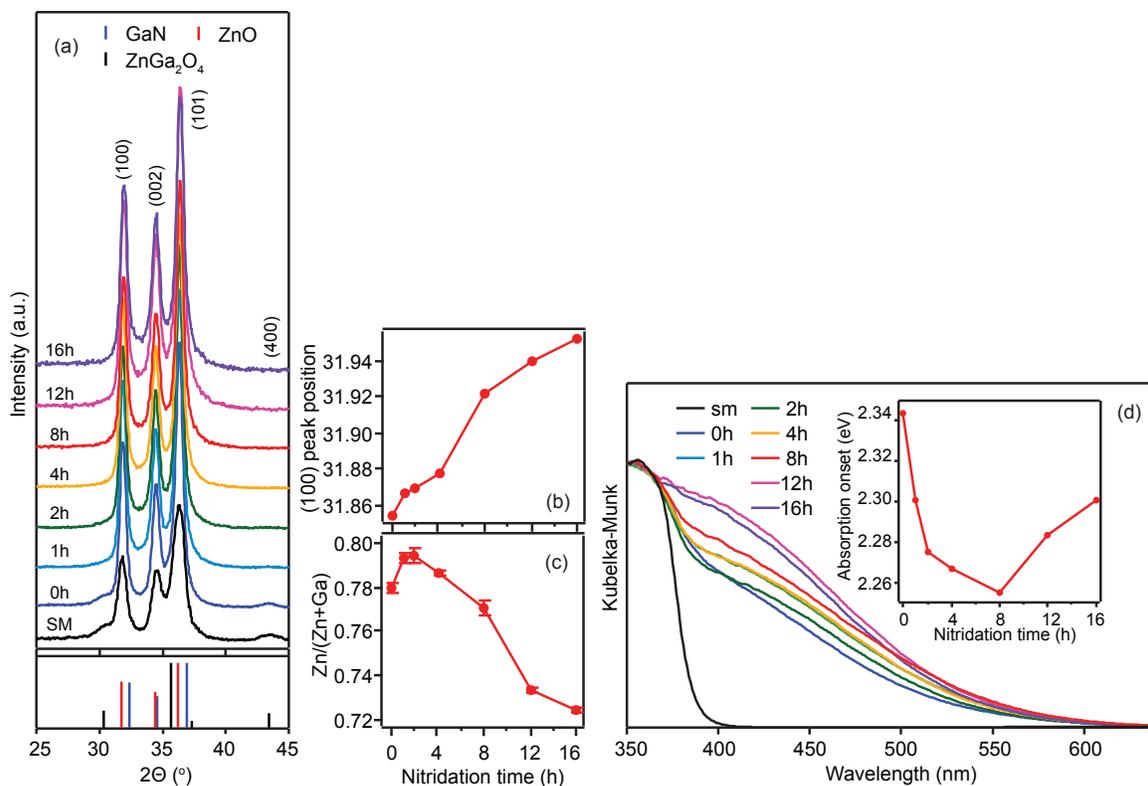


Figure S3. (a) Powder XRD patterns, (b) (100) peak position, (c) Elemental analysis from ICP-OES, and (d) Diffuse reflectance spectra (normalized at 350 nm) of the products from nitridation of a starting mixture ( $Zn/(Zn+Ga)=0.78$ ).

As shown in Figure S3, ZnO-rich starting mixture ( $Zn/(Zn+Ga)=0.78$ ) was nitrided for 0 - 16 hours. The XRD patterns of each nitrided product show that the spinel peaks of  $ZnGa_2O_4$  in the starting mixture quickly disappear, and the (100) peak of ZnO shifts to higher angle in 2 hours of nitridation, resulting from the conversion of spinel  $ZnGa_2O_4$  and wurtzite ZnO to wurtzite  $(Ga_{1-x}Zn_x)(N_{1-x}O_x)$ , similar to what we observed from the  $x=0.39$  sample set described in the manuscript. The shift of the wurtzite (100) peak was not drastic in this ZnO-rich sample set since the starting mixture contains much smaller amount of  $ZnGa_2O_4$  than that in the  $x=0.39$  sample set. Zn loss appeared to be significant (on the order of 10%) after 2 hours of nitridation in the  $x=0.78$  synthesis, which leads to the changes of the (100) peak position observed after 2 hours. The Zn loss is caused by reduction of ZnO to Zn under ammonia atmosphere, and subsequent volatilization of the Zn. This results in the peak shift towards GaN observed after 2 hours. In the diffuse reflectance spectra of the nitrided products, the absorption onsets rapidly shift to lower energy as the spinel  $ZnGa_2O_4$  and wurtzite ZnO convert to wurtzite  $(Ga_{1-x}Zn_x)(N_{1-x}O_x)$  in the same time period. In conclusion, the observations from both ZnO-low and ZnO-rich sample sets reveal the consistent reaction mechanism where the conversion of spinel  $ZnGa_2O_4$  to wurtzite occurs upon topotactic nucleation at a ZnO/  $ZnGa_2O_4$  interface, and this results in the red shift of absorption onsets.

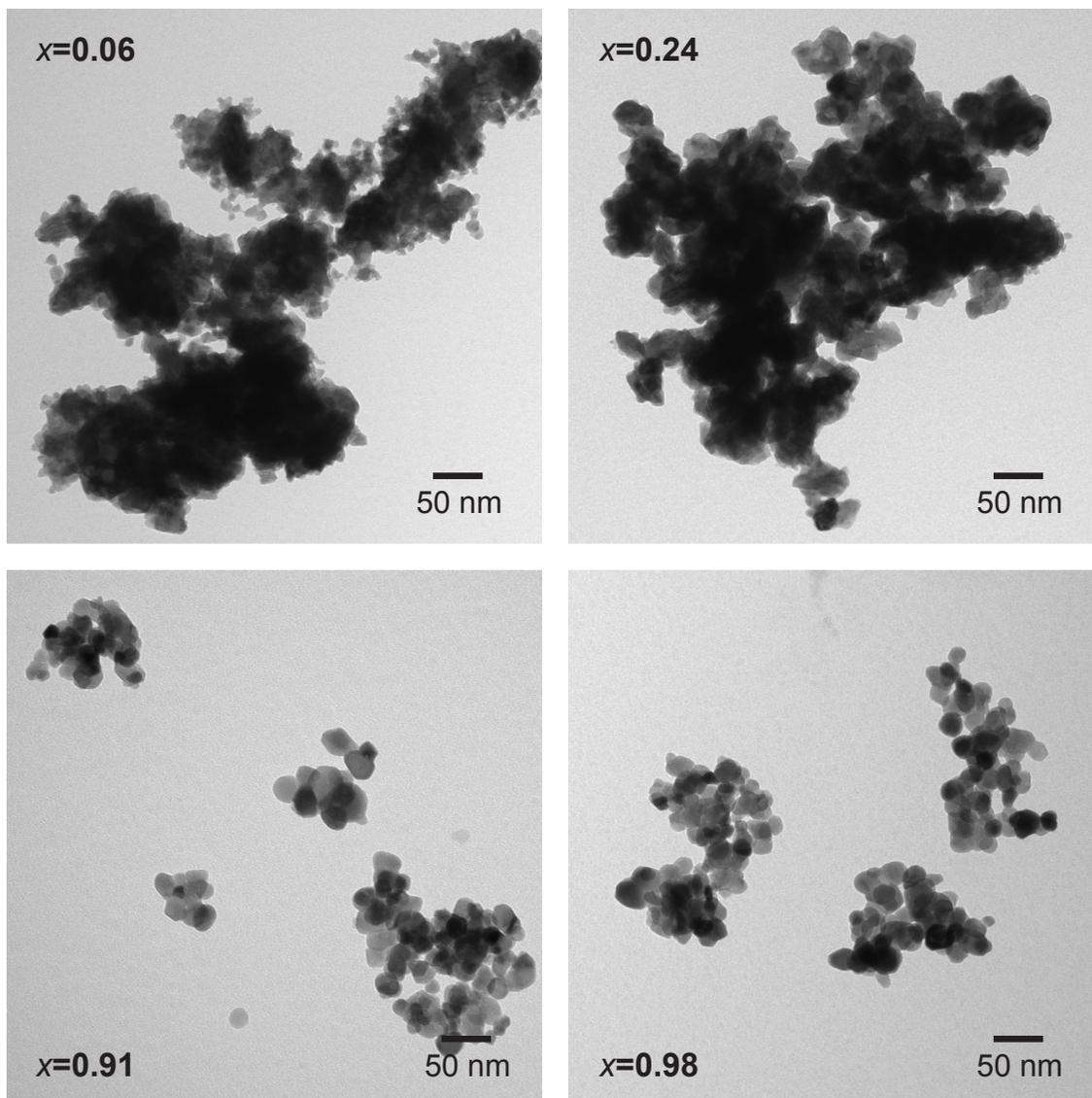


Figure S4. Low magnification TEM images of  $(\text{Ga}_{1-x}\text{Zn}_x)(\text{N}_{1-x}\text{O}_x)$ , ( $x=0.06, 0.24, 0.91, \text{ and } 0.98$ ).

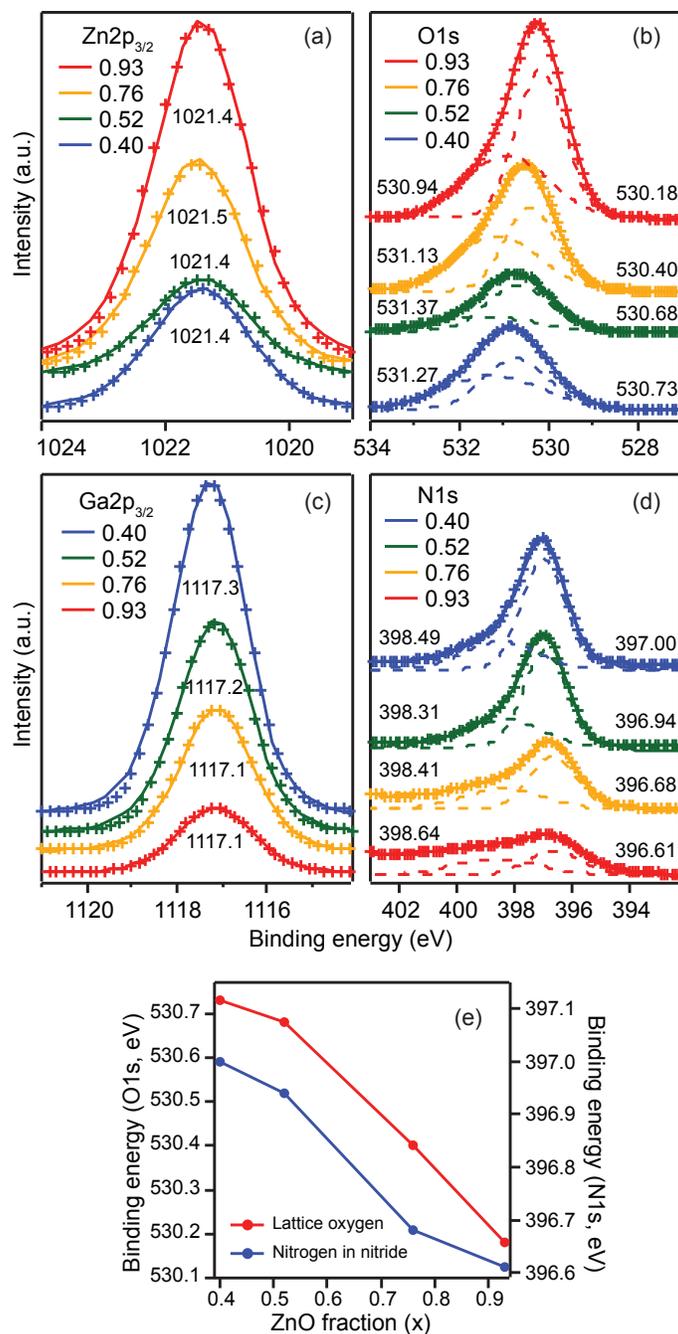


Figure S5. XPS spectra of the  $(\text{Ga}_{1-x}\text{Zn}_x)(\text{N}_{1-x}\text{O}_x)$  with  $x= 0.40, 0.52, 0.76,$  and  $0.93$  for (a)  $\text{Zn}2p_{3/2}$ , (b)  $\text{O}1s$ , (c)  $\text{Ga}2p_{3/2}$ , and (d)  $\text{N}1s$ . (e) Binding energy of lattice oxygen (red) and nitrogen in nitride ( $\text{N}^{3-}$ ) versus the  $x$  value.

Figure S5 shows the high-resolution XPS spectra for the  $\text{O}1s$  and  $\text{N}1s$  peaks of  $(\text{Ga}_{1-x}\text{Zn}_x)(\text{N}_{1-x}\text{O}_x)$  with  $x=0.40, 0.52, 0.76,$  and  $0.93$ . The  $\text{Zn}2p_{3/2}$  peaks of the  $(\text{Ga}_{1-x}\text{Zn}_x)(\text{N}_{1-x}\text{O}_x)$  appear at almost the same binding energy (1021.4–1021.5 eV) regardless of the composition, which is lower than the reference value of  $\text{ZnO}$  (1022.0 eV<sup>1</sup>) as shown in Figure S5a. This indicates that  $\text{Zn}$  in  $(\text{Ga}_{1-x}\text{Zn}_x)(\text{N}_{1-x}\text{O}_x)$  has more electron density than in  $\text{ZnO}$ . The same behavior was observed in bulk  $(\text{Ga}_{1-x}\text{Zn}_x)(\text{N}_{1-x}\text{O}_x)$  and was attributed to the presence of  $\text{Zn-N}$  bonding and

lower electronegativity of N than O.<sup>2</sup> The O1s peaks in Figure S5b were deconvoluted into two peaks that can be assigned to a crystal lattice oxygen (530.18–530.73 eV) and surface –OH group (531.13–531.37 eV).<sup>2</sup> The peaks of the lattice oxygen appear at lower energies with increasing  $x$ , as shown in Figure S5e. The peak shift with composition suggests the existence of Ga-O bonds as well as Zn-O bonds in the lattice and the amount of each bonding changes with the composition. Higher  $x$  samples contain less Ga-O bonding and more Zn-O bonding, leading to the movement of more electron density towards O due to lower electronegativity of Zn than Ga (electronegativity: 1.65 for Ga; 1.81 for Zn based on Pauling scale).<sup>3</sup> For Ga2p<sub>3/2</sub> peaks (Figure S5c), all the samples show similar peak position at 1117.1–1117.3 which are consistent with Ga2p<sub>3/2</sub> in GaN (1117.1 eV<sup>4</sup>). Because the reference peak of Ga2p<sub>3/2</sub> in Ga<sub>2</sub>O<sub>3</sub> (1117.5–1117.8<sup>5</sup>) is very close to the one in GaN, the possible presence of the Ga-O bonding as well as the Ga-N bonding cannot be excluded. The N1s peak of all the samples consists of two components (Figure S5d).<sup>6-9</sup> The peak of N1s at ~398.5 eV is similar to that of NH<sub>3</sub> and primary amines. The presence of the amine peak could be due to the NH<sub>3</sub> molecules adsorbed on the surface during the nitridation.<sup>8</sup> The other N1s peak appears at the lower binding energy (396.61–397.00 eV). We assign this peak to nitride (N<sup>3-</sup>) because the lattice nitrogen peaks of GaN and Zn<sub>3</sub>N<sub>2</sub> appear at 397 and 395.7 eV, respectively.<sup>1, 2, 4, 6-9</sup> The nitride peaks continuously shift to lower binding energy with increasing  $x$  values (see Figure S5e). Similar to the case of oxygen, this shift can be also explained by the existence of Zn-N and Ga-N bonds in the lattice and lower electronegativity of Zn than Ga. With increasing Zn content, more electron density moves toward N lowering its binding energy. While XPS analysis of bulk (Ga<sub>1-x</sub>Zn<sub>x</sub>)(N<sub>1-x</sub>O<sub>x</sub>) has been described previously for a narrow range of compositions,<sup>2, 7, 10</sup> composition-dependent XPS peak shifting over a broad range of compositions has not been reported before. The XPS data in Figure S5 is consistent with formation of Ga-O and Zn-N bonds in (Ga<sub>1-x</sub>Zn<sub>x</sub>)(N<sub>1-x</sub>O<sub>x</sub>) nanocrystals, in agreement with XRD data in Figure 4.

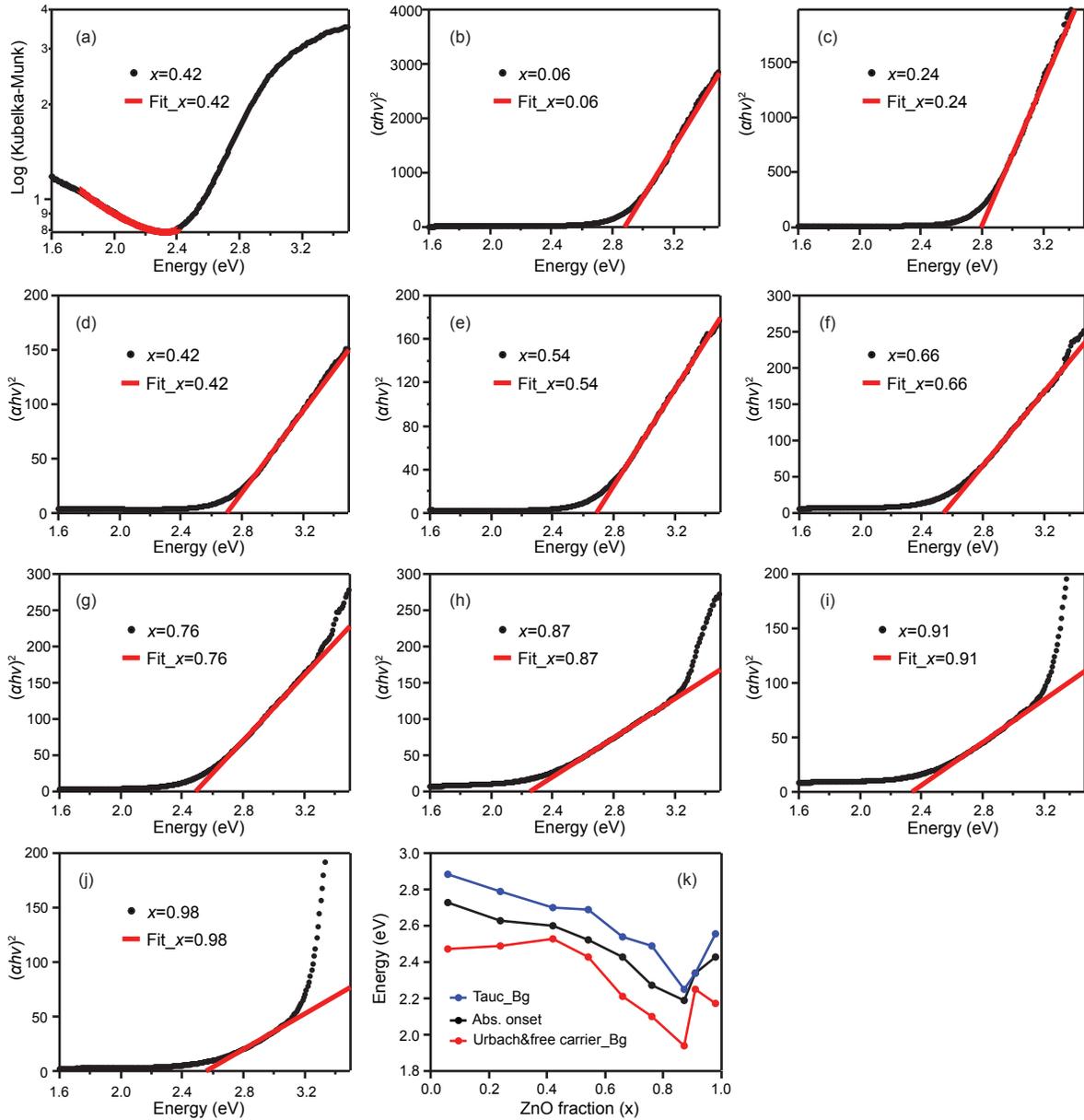


Figure S6. Band gap determination of  $(\text{Ga}_{1-x}\text{Zn}_x)(\text{N}_{1-x}\text{O}_x)$  from (a) fitting the below-band gap absorption features for  $x=0.42$  sample as previously described.<sup>11</sup> The red line indicates a fit to  $\alpha(E) = A \times e^{(E-E_g)/E_u} + B \times E^{-3} + C$ , where  $A$ ,  $B$ , and  $C$  are constants,  $E_g$  is band gap energy, and  $E_u$  is Urbach energy. The value of  $E_g$  determined by this method is highly dependent on the details of the fit, such as the energy limits. and (b-j) Tauc plots of  $(\alpha h\nu)^2$  against  $h\nu$ . Tauc plot were fit with a straight line (red) below the energy of the absorption feature characteristic of ZnO (3.2 eV). The value of  $E_g$  is the x-intercept of the red fit line (k) Band gap energy determined from the direct band gap absorption (Tauc plot), absorption onset, and below-band gap absorption (free carrier + Urbach tail).

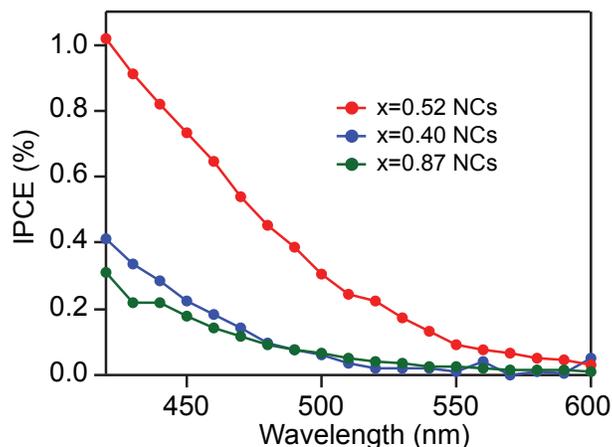


Figure S7. Incident photon-to-current efficiency (IPCE) spectra of nanoscale  $(\text{Ga}_{1-x}\text{Zn}_x)(\text{N}_{1-x}\text{O}_x)$  ( $x=0.40, 0.52,$  and  $0.87$ ) obtained from sulfite oxidation in pH 7 phosphate buffer.

## References

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